SiNx Films by PECVD#2 (Advanced Vacuum)

Pressure (mT)	LF (187kHz; 80W) Duration Time (s)	HF	Gas Flow-rate (sccm)				Donosition	Donosition		Average	Ctandard
		(13.56MHz;30W) Duration Time (s)	SiH4 (2% in He)	NH3	N2	Deposition Time (s)	Deposition Thickness (A)	Deposition Rate (A/m)	Refractive Index	Average Stress (MPa)	Standard Deviation (MPa)
800	0.5	6	1000	16	980	1749	2398	82	1.974	281	na
800	1	6	1040	18	980	1800	2397	80	1.98	112	27
800	1.5	6	1040	18	980	1929	2596	81	1.962	-113	15
800	1.25	6	1040	18	980	1800	2414	80	1.964	-62	14
800	0	HF only	1040	17	980	1535	2225	87	2.003	454	19
800	LF only	0	1040	5	980	1940	2448	76	1.984	-2010	134
800	2	6	1040	14.4	980	1705	2245	79	1.979	-315	69
800	1.66	6	1040	16	980	2100	2835	81	1.967	-257	186
800	4.031	6	900	10	980	1800	2377	79	1.972	-677	26
800	6	6	900	10	980	2100	2289	65	1.973	-659	64
800	6	4	900	10	980	1800	2301	77	1.963	-1100	36
800	1.2	8.8	1040	15	980	1800	2218	74	2.005	259	37
800	1.6	6	1040	14	980	2100	2384	68	1.996	51	79
800	2.512	5.088	1040	14	980	2100	2472	71	1.974	-457	69
800	2.056	5.544	1040	14	980	2100	2620	75	1.976	-386	86
800	1.828	5.772	1040	14	980	2100	2320	66	2.007	74.82	81
800	1.942	5.658	1040	14	980	2100	2318	66	2.003	-4.77	80
800	2	5.6	1040	14	980	2100	2635	75	1.978	-350	98
800	1.971	5.629	1040	14	980	2100	2535	72	1.984	-303.71	98